

US DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEAPPLICANT: MARTIN RICHARDSON  
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA  
PRODUCED FROM LIQUID METAL SOLUTIONSjc978 U.S. PTO  
09/081620  
06/14/01LIST OF ART CITED BY APPLICANTU.S. PATENT DOCUMENTS

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AB	4,328,464	05/04/82	Piviotto	330	4.3	02/07/80
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AG	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
AH	5,142,297	08/25/92	Eijkman et al.	346	1.1	03/26/90
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11040 U.S. PTO  
09/883420  
06/18/01

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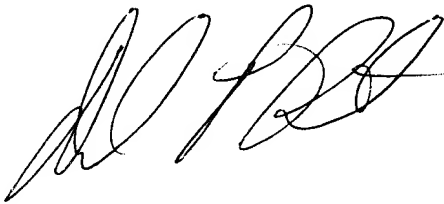
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6/13/02